

Title (en)  
FABRICATION METHOD

Title (de)  
HERSTELLUNGSVERFAHREN

Title (fr)  
METHODE DE FABRICATION

Publication  
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Application  
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Abstract (en)  
[origin: WO2005031855A1] Described is a method for forming a multilevel structure on a surface. The method comprises: depositing a curable liquid layer (200) on the surface; pressing a stamp (120) having a multilevel pattern therein into the liquid layer to produce in the liquid layer a multilevel structure defined by the pattern; and, curing the liquid layer to produce a solid layer having the multilevel structure therein. Mechanical alignment may be employed to enhance optical alignment of the stamp relative to the substrate via a plurality of spaced protrusions on the substrate on which the structure is to be formed and complementary recesses in the patterning of the stamp.

IPC 8 full level  
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